IN THE CLAIMS:

Please amend the claims as shown below.

1. (Currently Amended) A field effect transistor comprising at least a substrate, an organic semiconductor layer, an insulating layer, and a conductive layer, wherein the insulating layer comprises a cured product of a phenol resin represented by a following general formula (1):

(wherein, wherein R^1 , R^2 and R^3 are each independently at least one selected from the group consisting of hydrogen atom, halogen atom, hydroxymethyl group, alkyl group having 1 to 12 carbon atoms, alkenyl group, alkinyl group, alkoxyl group, alkylthio group, and alkyl ester group, X^1 and X^2 are each independently at least one selected from the group consisting of hydrogen atom, alkyl group having 1 to 12 carbon atoms, alkenyl group, alkinyl group, and aryl group, and n is an integer of 0 to $\frac{2,000}{2,000}$.

- 2. (Original) The field effect transistor according to claim 1, wherein the conductive layer comprises a gate electrode, a source electrode, and a drain electrode, the insulating layer includes a gate insulating layer, and the gate insulating layer is a cured product of a phenol resin represented by the above general formula (1).
- 3. (Original) The field effect transistor according to claim 2, wherein the thickness of the gate insulating layer is 100 nm to $1\mu m$.
- 4. (Original) The field effect transistor according to any one of claims 1 to 3, wherein part or all of the conducive layer comprises an agglomerate of conductive fine particles having a primary particle diameter of 5 nm to $2\mu m$.
- 5. (Currently Amended) A process for producing a field effect transistor comprising a substrate, an organic semiconductor layer, an insulating layer, and a conductive layer, the process comprising the steps of:

coating a thermosetting resin composition containing at least a phenol resin represented by the following general formula (1):

(wherein, wherein R¹, R² and R³ are each independently at least one selected from the group consisting of hydrogen atom, halogen atom, hydroxymethyl group, alkyl group having 1 to 12 carbon atoms, alkenyl group, alkinyl group, alkoxyl group, alkylthio group, and alkyl ester group, X¹ and X² are each independently at least one selected from the group consisting of hydrogen atom, alkyl group having 1 to 12 carbon atoms, alkenyl group, alkinyl group, and aryl group, and n is an integer of 0 to 2,000.) and 2000; and heating [[it]] the thermosetting resin to form the insulating layer.

- 6. (Original) The process for producing a field effect transistor according to claim 5, wherein part or all of the conductive layer is formed by applying a solution, dispersion, or paste of a conductive material or a precursor of the conductive material and heating it.
- 7. (Original) The process for producing a field effect transistor according to claim 5, wherein the softening point of the phenol resin contained in the thermosetting resin composition is in the range of 70 to 130°C.